

(b) Amendment to the Claims

Please amend claim 12 as follows. The status of all the claims is listed below.

1. - 11. (Cancelled)

12. (Currently Amended) A plasma treatment apparatus for individually treating a plurality of reactors having different impedances comprising:

a plurality of movable reactors each having an evacuable interior where at least one treatment substrate is set, each movable reactor and having impedances impedance different from each other and each movable reactor conducting a different treatment from each other;

a high-frequency power supply means for supplying high-frequency power into each movable reactor having been internally-evacuated, to cause glow discharge to take place in the movable reactor, said high-frequency power supply means having a connecting portion for connecting with one of the movable reactors;

an impedance regulation means provided on the side of each movable reactor to regulate the impedances of each reactor; and

a moving means for moving each of the movable reactors, wherein each of the movable reactors and the high-frequency power supply means are provided separately and wherein one impedance regulation means is provided between a the connecting portion of the high-frequency power supply means spaced on the side exterior of the moveable reactor and an electrode which is spaced on the side interior of the moveable movable reactor.

13. (Previously Presented) The plasma treatment apparatus of claim 12,
wherein the substrate is a substrate for an electrophotographic photosensitive member.

14. - 25. (Cancelled)